

FORM: PTO-1449 (REV: 7-80)	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	Atty Docket No: 98-1191.01	Serial No:
INFORMATION DISCLOSURE STATEMENT BY APPLICANT  (37 CFR 1.98(b)) (use several sheets if necessary)		Applicant: Gurtej S. Sandhu	
		Filing Date: November 9, 2001	Group:

jc835 U.S. PTO  
10/010895  
11/09/01

## U.S. PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Name	Class	Subclass
L.T.M.E.	AA 5,985,770	11/16/99	Sandhu et al.	438	787
L.T.M.E.	AB 5,880,007	03/09/99	Varian et al.	438	427
L.T.M.E.	AC 5,872,058	02/16/99	Van Cleemput et al.	438	692
L.T.M.E.	AD 5,872,052	02/16/99	Iyer	438	622
L.T.M.E.	AE 5,858,869	01/12/99	Chen et al.	438	597
L.T.M.E.	AF 5,814,564	09/29/98	Yao et al.	438	723
L.T.M.E.	AG 5,804,506	09/08/98	Haller et al.	438	649
L.T.M.E.	AH 5,641,545	06/24/97	Sandhu	427	573
L.T.M.E.	AI 5,633,211	05/27/97	Imai et al.	438	760
L.T.M.E.	AJ 5,485,035	01/16/96	Lin et al.	257	637
L.T.M.E.	AK 5,448,097	09/05/95	Mizushima et al.	257	435

## FOREIGN PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Country	Class	Subclass	Translation	
						Yes	No
L.T.M.E.	AL EP 0 875 930 A2	11/04/98	Europe	H01L 21	768	<input type="checkbox"/>	<input type="checkbox"/>
L.T.M.E.	AM EP 0 875 929 A2	11/04/98	Europe	H01L 21	768	<input type="checkbox"/>	<input type="checkbox"/>
	AN					<input type="checkbox"/>	<input type="checkbox"/>
	AO					<input type="checkbox"/>	<input type="checkbox"/>
	AP					<input type="checkbox"/>	<input type="checkbox"/>
	AQ					<input type="checkbox"/>	<input type="checkbox"/>

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## OTHER ART (including author, title, date, pertinent pages, etc.)

L.T.M.E.	AR	Sabine Penka, et al., <i>Integration Aspects of Flowfill and Spin-on-Glass Process for Sub-0.35µm Interconnects</i> , PROCEEDINGS OF THE IEEE 1998 INTERNATIONAL INTERCONNECT TECHNOLOGY CONFERENCE, at 271-273 (1998).
L.T.M.E.	AS	U. Höckele, et al., <i>Flowfill-Process as a New Concept for Inter-Metal-Dielectrics</i> , MATERIALS SCIENCE FORUM, at 235-238 (1998).
L.T.M.E.	AT	K. Beekmann, et al., <i>Sub-micron Gap Fill and In-Situ Planarisation using Flowfill™ Technology</i> , CONFERENCE PROCEEDINGS ULSI XI, MATERIALS RESEARCH SOCIETY, at 137-143 (1996).

Examiner: Lynette T. Veng-Everetti	Date Considered: 11/24/2004
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EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication with applicant.

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		Filing Date:	Group:
		Concurrently Herewith	

**U.S. PATENT DOCUMENTS**

Examiner Initial	Document Number	Date	Name	Class	Subclass	
L.T.M.E.	AA 5,302,233	04/12/94	Kim et al.	156	636	
L.T.M.E.	AB 4,474,831	10/02/84	Downey	438	800	
L.T.M.E.	AC 4,016,017	04/05/77	Aboaf et al.	438	441	
	AD					
	AE					
	AF					
	AG					
	AH					
	AI					
	AJ					
	AK					

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	AL					Yes	No
	AM					<input type="checkbox"/>	<input type="checkbox"/>
	AN					<input type="checkbox"/>	<input type="checkbox"/>
	AO					<input type="checkbox"/>	<input type="checkbox"/>
	AP					<input type="checkbox"/>	<input type="checkbox"/>
	AQ					<input type="checkbox"/>	<input type="checkbox"/>

Initial

**OTHER ART** (including author, title, date, pertinent pages, etc.)

L.T.M.E.	AR		A. Hass Bar-Ilan, et al., <i>A Comparative Study of Sub-micron Gap Filling and Planarization Techniques</i> , PROCEEDINGS OF THE SPIE - THE INTERNATIONAL SOCIETY FOR OPTICAL ENGINEERING, at 277-288 (1995).
L.T.M.E.	AS		Wolf et al., <i>Silicon Processing for the VLSI Era vol. 1: Process Technology</i> , 1986, Lattice Press, California, pp. 190
	AT		

Examiner: <i>Lynette T. Umeg-Eumini</i>	Date Considered: <i>11/29/2004</i>
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